

Title (en)
Illumination system

Title (de)
Beleuchtungssystem

Title (fr)
Système d'illumination

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Application
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Abstract (en)
[origin: WO03017003A2] The invention relates to a diaphragm (1) for an integrator unit of a micro-lithography projection exposure system. Said diaphragm (1) comprises a diaphragm opening (3), which is symmetrical in relation to a first axis of symmetry (5). The widths of the diaphragm aperture (3) in the direction of the axis of symmetry (5) are dependent on the distance of y from the first axis of symmetry (5), said widths being greater than or equal to the width when y=0. The diaphragm (1), together with a cylindrical integrator, forms an integrator unit, which is located in an illumination system.

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